

Refine Search

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Terms	Documents
aluminum adj nitrate and copper and dielectric and (tantalum adj nitride or tantalum or ta or tan) and first adj5 (cmp or polishing or planarizing) adj3 (slurry or step) and second adj5 (cmp or polishing or planarizing) adj3 (slurry or step)	2

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	<i>DB=PGPB,USPT,USOC,EPAB,JPAB,DWPI,TDBD; PLUR=YES; OP=ADJ</i>		
<u>L30</u>	aluminum adj nitrate and copper and dielectric and (tantalum adj nitride or tantalum or ta or tan) and first adj5 (cmp or polishing or planarizing) adj3 (slurry or step) and second adj5 (cmp or polishing or planarizing) adj3 (slurry or step)	2	<u>L30</u>
<u>L29</u>	ammonium adj nitrate and copper and dielectric and (tantalum adj nitride or tantalum or ta or tan) and first adj5 (cmp or polishing or planarizing) adj3 (slurry or step) and second adj5 (cmp or polishing or planarizing) adj3 (slurry or step)	10	<u>L29</u>
<u>L28</u>	(hydroxylamine adj nitrate or hydrazine) and copper and dielectric and (tantalum adj nitride or tantalum or ta or tan) and first adj5 (cmp or polishing or planarizing) adj3 (slurry or step) and second adj5 (cmp or polishing or planarizing) adj3 (slurry or step)	3	<u>L28</u>
	<i>DB=PGPB,USPT; PLUR=YES; OP=ADJ</i>		
<u>L27</u>	L25 and (polish or polishing) adj stop	0	<u>L27</u>

<u>L26</u>	L25 and (phase adj one or first or initially or initial) adj3 (cmp or chemical adj mechanical adj (polishing or polish or planarization)) adj2 (slurry or step or composition)	1	<u>L26</u>
<u>L25</u>	L24 and (hydroxylamine or hydroxyl adj amine or ammonium adj nitrate or aluminum adj nitrate or hydrazine)	14	<u>L25</u>
<u>L24</u>	L21 or L22 or L23	38	<u>L24</u>
<u>L23</u>	20020062600 or 20010037821	2	<u>L23</u>
<u>L22</u>	US-6149696-\$.DID. OR US-6299795-\$.DID. OR US-6117775-\$.DID. OR US-6461227-\$.DID. US-6156661-\$.DID. OR US-6140239-\$.DID. OR US-6117733-\$.DID. OR US-6063306-\$.DID. OR US-5954997-\$.DID. OR US-5981454-\$.DID. OR US-5899740-\$.DID. OR US-5897375-\$.DID. OR US-5863307-\$.DID. OR US-5858813-\$.DID. OR US-5840629-\$.DID. OR US-5780358-\$.DID. OR US-5770517-\$.DID. OR US-5735963-\$.DID. OR US-5614444-\$.DID. OR US-	4	<u>L22</u>
<u>L21</u>	5575837-\$.DID. OR US-5527423-\$.DID. OR US-5354490-\$.DID. OR US-5340370-\$.DID. OR US-5225034-\$.DID. OR US-4724042-\$.DID. OR US-4556449-\$.DID. OR US-4013758-\$.DID. OR US-3592773-\$.DID. OR US-3410802-\$.DID. OR US-3385682-\$.DID. OR US-3137600-\$.DID. OR US-6293848-\$.DID. OR US-6398827-\$.DID. OR US-4959113-\$.DID. OR US-4204013-\$.DID. OR US-5281311-\$.DID.	32	<u>L21</u>
<i>DB=PGPB,USPT,USOC,EPAB,JPAB,DWPI,TDBD; PLUR=YES; OP=ADJ</i>			
<u>L20</u>	L19 and (phase adj one or first or initially or initial) adj3 (cmp or chemical adj mechanical adj (polishing or polish or planarization)) adj2 (slurry or step or composition)	5	<u>L20</u>
<u>L19</u>	abrasive and aluminum adj nitrate and copper and (dielectric or insulating) and (tantalum or tantalum adj nitride)	70	<u>L19</u>
<u>L18</u>	abrasive and aluminum adj nitrate and copper and (dielectric or insulating) and (tantalum or tantalum adj nitride) and (polishing or polish)adj stop	0	<u>L18</u>
<u>L17</u>	abrasive and (ammonium or aluminum) adj4 nitrate and copper and dielectric and (tantalum or tantalum adj nitride) and (phase adj one or first or initially or initial) adj3 (cmp or chemical adj mechanical adj (polishing or polish or planarization)) adj2 (slurry or step or composition)	44	<u>L17</u>
<u>L16</u>	L14 and (phase adj one or first or initially or initial) adj3 (cmp or chemical adj mechanical adj (polishing or polish or planarization)) adj2 (slurry or step or composition)	4	<u>L16</u>
<u>L15</u>	L12 and (phase adj one or first or initially or initial) adj3 (cmp or chemical adj mechanical adj (polishing or polish or planarization)) adj2 (slurry or step or composition)	21	<u>L15</u>
<u>L14</u>	L13 and (cmp or chemical adj mechanical adj (polish or polishing))	54	<u>L14</u>
<u>L13</u>	hydrazine and copper and dielectric and (tantalum or tantalum adj nitride) and (nitrate or nitric adj acid)	135	<u>L13</u>
<u>L12</u>	(hydroxylamine or hydroxyl adj amine) near4 nitrate and copper and dielectric and (tantalum or tantalum adj nitride) and (nitrate or nitric adj acid)	41	<u>L12</u>
<u>L11</u>	L10 not L9	15	<u>L11</u>
<u>L10</u>	copper same (barrier adj layer or tantalum) and (oxidizer or oxidizing) with (hydroxylamine nitrate or hydrazine)	22	<u>L10</u>
	copper same dielectric same (barrier adj layer or tantalum) and (oxidizer or		

<u>L9</u>	oxidizing) with (hydroxylamine nitrate or hydrazine)	7	<u>L9</u>
	((phase one or first or initial) near3 (polishing or planarizing or planaization or polished or planarized) and (phase two or second or subsequent or final) near3		
<u>L8</u>	(polishing or planarizing or planaization or polished or planarized) and copper same dielectric same (barrier adj layer or tantalum) and (oxidizer or oxidizing) with (ammonium or aluminum) adj (nitrate or salt)).clm.	0	<u>L8</u>
	(phase one or first or initial) near3 (polishing or planarizing or planaization or polished or planarized) and (phase two or second or subsequent or final) near3		
<u>L7</u>	(polishing or planarizing or planaization or polished or planarized) and copper same dielectric same (barrier adj layer or tantalum) and (oxidizer or oxidizing) with (ammonium or aluminum) adj (nitrate or salt)	28	<u>L7</u>
	(phase one or first or initial) near3 (polishing or planarizing or planaization or polished or planarized) and (phase two or second or subsequent or final) near3		
<u>L6</u>	(polishing or planarizing or planaization or polished or planarized) and copper same dielectric same (barrier adj layer or tantalum) and (oxidizer or oxidizing) with nitrate	85	<u>L6</u>
<u>L5</u>	L4 and copper same dielectric same (barrier adj layer or tantalum)	12	<u>L5</u>
	(phase one or first or initial) near3 (polishing or planarizing or planaization or polished or planarized) and (phase two or second or subsequent or final) near3		
<u>L4</u>	(polishing or planarizing or planaization or polished or planarized) and (hydroxylamine nitrate or han or hydrazine)	138	<u>L4</u>
	(first or initial) near3 (polishing or planarizing or planaization or polished or planarized) and (second or subsequent or final) near3 (polishing or planarizing or planaization or polished or planarized) and (hydroxylamine nitrate or han or hydrazine)		
<u>L3</u>	(polishing or planarizing or planaization or polished or planarized) and (second or subsequent or final) near3 (polishing or planarizing or planaization or polished or planarized) and (hydroxylamine nitrate or han or hydrazine)	138	<u>L3</u>
<u>L2</u>	L1 and (ammonium nitrate or aluminum nitrate)	8	<u>L2</u>
	(first or initial) with (polishing or planarizing or planaization or polished or planarized) and (second or subsequent or final) with (polishing or planarizing or planaization or polished or planarized) and (hydroxylamine nitrate or han)		
<u>L1</u>	(polishing or planarizing or planaization or polished or planarized) and (second or subsequent or final) with (polishing or planarizing or planaization or polished or planarized) and (hydroxylamine nitrate or han)	388	<u>L1</u>

END OF SEARCH HISTORY